

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (original) A resist composition comprising an alkaline soluble novolak resin, a naphthoquinonediazide photosensitive compound and an organic solvent, characterized in that the organic solvent comprises benzyl alcohol or its derivatives.
2. (original) The resist composition according to claim 1, characterized in that the organic solvent comprises 1 % by weight to 35 % by weight of benzyl alcohol or its derivatives.
3. (original) A photosensitive resist composition comprising an alkaline soluble acrylic resin or novolak resin, a strong acid or a radical generating compound by irradiating UV ray, a crosslinker and an organic solvent, characterized in that the organic solvent comprises benzyl alcohol or its derivatives.
4. (currently amended) The resist composition according to claim ~~[[1]]~~ 3, characterized in that the organic solvent comprises 1 % by weight to 35 % by weight of benzyl alcohol or its derivatives.
5. (original) An organic solvent for removing a resist, comprising benzyl alcohol or its derivatives.